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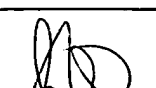

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	Shallow Trench Isolation, "Trench Isolation," http://courses.nus.edu.sg/course/phy/ pgs. 1-4
	Institute of Microelectronics - Deep Submicron - Ultra-thin gate oxides, "Deep Submicron", http://www.ime.org.sg/deep/deep_ultra.htm >, pgs. 1-2
	SNP Applications/Shallow Trench Isolation (STI), "SNP 9000 Applications", http://www.surfaceinterface.com/snapappsSTI.html >, pgs. 1-2
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	11/16/02

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U.S. PATENT DOCUMENTS

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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

Hitachi America, Ltd. Semiconductor Equipment Group ..., "Customizable Shallow Trench Isolation," pg. 1 of 1

EXAMINER

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